

Abstract

A substrate treatment device includes: a substrate holding unit including a plate-shaped holding table that rotatably holds a substrate (10) so that a surface of the substrate on which the fine patterns (11) are formed faces downward, and a plurality of holding pins provided on the holding table to hold an outer periphery of the substrate (10) at a plurality of points; a heater that heats the substrate (10); a cover that internally houses the substrate holding unit and the heater, and forms a treatment chamber; a pump that exhausts the treatment chamber to make a negative-pressure atmosphere; an inert gas supply port that faces an opposite side surface opposite to the surface with the fine patterns (11) formed thereon, and supplies inert gas into the treatment chamber; and a nozzle to jet a cleaning solution toward the surface with the fine patterns (11) formed thereon and a gas exhaust port to communicate with the pump, the nozzle and the gas exhaust port being provided on the holding table.